

<b>Notice of References Cited</b>	Application/Control No. 10/690,573		Applicant(s)/Patent Under Reexamination SONG ET AL.	
	Examiner Steven H. Rao		Art Unit 2814	Page 1 of 2

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,859,254	02-2005	Kim et al.	349/190
	B	US-6,914,641	07-2005	Choo et al.	349/38
	C	US-5,838,314	11-1998	Neel et al.	725/8
	D	US-5,919,606	07-1999	Kazlas et al.	430/321
	E	US-5,963,689	10-1999	Hesselbom, Hjalmar	385/53
	F	US-6,037,044	03-2000	Giri et al.	428/209
	G	US-6,057,896	05-2000	Rho et al.	349/42
	H	US-6,330,043	12-2001	Kikkawa et al.	349/43
	I	US-6,414,729	07-2002	Akiyama et al.	349/38
	J	US-6,597,415	07-2003	Rho et al.	349/42
	K	US-6,707,511	03-2004	Kim et al.	349/38
	L	US-6,794,228	09-2004	Kim, Hong-Jin	438/149
	M	US-6,862,050	03-2005	Rho et al.	349/44

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Je-Hsiung Lan et al., 'Planarization technology Of a Si:H TFTs for Am-LCDs' , July 1988, SPIE Vol. 3421, SPIE conference On Display Technologies II , Taipei, Taiwan, pages 170-182.
	V	Phillip E. Garrou et al. , ' Stress-Buffer and Passivation Processes for SI and GaAs IC's and Passive Components Using Photosensitive BCB: Process Technology and Reliability Data ' IEEE Transactions on AdvancedPackaging , Vol. 22 No.3 August 1999, pages
	W	M.J. Radler et al., " A2.4 : Cyclotene Advanced Electronics resins for High-Aperture AMLCD Applications " , 1996 , SID 96 Applications Digest pages 33-36
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

<b>Notice of References Cited</b>	Application/Control No. 10/690,573	Applicant(s)/Patent Under Reexamination SONG ET AL.	
	Examiner Steven H. Rao	Art Unit 2814	Page 2 of 2

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,780,871	07-1998	den Boer et al.	257/59
	B	US-5,287,208	02-1994	Shimoto et al.	349/123
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.